# **Overview of WLBI system approaches**

Larry Gilg MCC Austin, Texas (512)338-3748

0.0

### **Trends in the Electronics Industry**

### IC Technology

- —Higher pin count
- —Higher power
- -Higher speed

### Major Drivers

- -Cost/Performance
- —Quality
- —Time-to-Market
- -Product Miniaturization, i.e. lighter, thinner, shorter, and smaller



# IC quality & reliability

### Test

- —Finds manufacturing defects that cause failure
- -Not feasible to search for all potential defects
- —One second on VLSI tester 2¢ to 15¢
  - » Exhaustive testing all combinations not economically feasible

### Burn-in

- -Stress causes weak devices to fail
- —Temperature stress
- -Voltage stress

### Test during burn-in

- -Long cycle functional testing is time-consuming
  - » Trend to offload to lower cost TDBI systems

# **Burn-in Cost Trend is Not Sustainable**

- Burn-in is a requirement for latest generations of VLSI devices
  - -New failure modes emerging due to shrinking geometries
  - -Researchers have failed to find an effective alternative
- Show stopper for many applications dependent on advanced packaging (i.e., KGD)



## Wafer Level Probing Lowers Burn-in Cost

- MCC cost models predict 50% cost savings for wafer level burn-in wrt current practice
  - -Other savings also significant
    - » Reduced IC fab/assembly/test cycle time, lower WIP
    - » Improved reliability feedback and control
    - » Enables new paradigm for assembly & test
- Full wafer probing for IC burn-in/test is achievable now
- Key components of Wafer Level Burn-in/Test (WLBT) system now coming into focus

# **IC "Back-end" Processes**

Wafer Fab



# **WLBT Cost Comparison**

- Fixed quantity of product each year
- 1 Meg FSRAM product
- Have sufficient capacity to keep product moving



# **WLBI Cost Saving**



- Graph shows cost of scrapping packages
- Assumes 80% final test yield, 2%
  burn-in fallout

| IC Product        | Final Test Yield |  |  |
|-------------------|------------------|--|--|
| 8-Bit MPU         | 95%              |  |  |
| 20,000 Gate Array | 90%              |  |  |
| 4M DRAM           | 95%              |  |  |
| 16M DRAM          | 90%              |  |  |
| 64M DRAM          | 75%              |  |  |
| 4K GaAs SRAM      | 80%              |  |  |
| 32-Bit MPU (386)  | 90%              |  |  |
| 32-Bit MPU (P54C) | 75%              |  |  |

<u>-Typical Final Test Yields</u>

MAG

# WLBT Value Added

Laser repair of burn-in fails is feasible after wafer level burn-in, but not available after pkg burn-in

### Assumptions

- 50% repairability of burn-in fails
- **Distribute ASP** of repaired die over population



0.0

9

1992

1600

1200

600

400

# **Additional WLBT Benefits**

### Fully Automatable

- -Reduce load/unload time
- -WLBT fits into highly automated IC assembly processes
  - » Potential for inventory reduction
  - » Cycle time improvements

### Keep from packaging (or shipping) weak devices

- -Yield loss at WLBT recoverable by laser repair
- -Early identification of "rogue" lots
- —Enabler for "single insertion" test/screening
  - » All die fully conditioned at wafer level
  - » Solution for KGD (Flip-chip)

### Rapid reliability feedback on wafer/lot basis

—Improves time-to-volume

### Eliminate traditional wafer probe step

-Massively parallel test during burn-in reduces time spent on expensive VLSI tester

# Wafer Burn-in Worldwide

### WBI Technology for Ram's\*

- -Memory Cell DC Stress to screen Bit Failures
- -Entire RAM Dynamic Stress for remaining failures

### WBI suppliers

- -Espec
- —Asia Electronics

### Several captive programs

- -Some IC manufacturers developing hardware
  - » Cost effective KGD
  - » Reduce cycle time
  - » Improved reliability feedback
  - » Potential for laser repair of DRAM burn-in fails

\* Furayama, et al. Wafer Burn-in (WBI) Technology for RAM's —IEDM-93

# Hypothetical 200mm Wafer Parameters

| Die:         | 652    |  |  |
|--------------|--------|--|--|
| Signal Pads: | 18,908 |  |  |
| Power Pads:  | 2608   |  |  |
| Total Pads:  | 21,516 |  |  |
| Total Power: | 650 W  |  |  |

### Feasibility Criteria Target Product Specification

### Attribute

Diameter Pad Metallurgy Minimum Passivation Well (Pad) Size Maximum Passivation Well Depth Minimum Pad Pitch Maximum Pad Density Maximum Z Variation, Pad-to-Pad Maximum Power Density 200mm Aluminum/Sn-Pb

75μ Χ 75μ

8.0  $\mu$ m 150 $\mu$  peripheral, 200 $\mu$  array 150 pads/cm<sup>2</sup>

1.0μm 5 W/cm2

Temperature Range Maximum Burn-In Time Clock Frequency 25ÞC - 150ÞC 168 hrs DC - 20 Mhz

# Feasibility Criteria Target Probe Coupon

#### Attribute

**Probe Coupon Diameter Dimensional Tolerance Maximum Probe Point Size Maximum Probe Point Current** Maximum Probe Point Resistance **Minimum Reuses, Same Pad Minimum Lifetime, Reuses Minimum Lifetime, Hours at Temp. Maximum Isolation Resistor Density Isolation Resistor Values** Max. Isolation Resistor Voltage Drop Max. Unisolated Signal Line Res. Max. Voltage Variation, VCC to Grnd **Power Isolation** 

### **Decoupling Capacitors**

### **Specification**

250mm  $+/-12\mu m$  absolute 25µm X 25µm 100mA 1.0ž 3 200 5000 150 resistors/cm<sup>2</sup> 5kž - 20kž 7.5V100ž 5% Must be provided. Max. 3 die/cm<sup>2</sup> Must be provided as needed

# **WLBT Challenges**

### Probe card

-High density interconnect

-CTE matching of probe to silicon

- —Co-planar probe tips
- —Uniform, "low" resistance contacts to aluminum pads/solder bumps

### Probe card environment

- -Precise alignment of probe to wafer
- —Uniform force delivery of probes to wafer
- -Mechanically decouple probe card from system
  - » Cte matched components independent of non-Cte matched components
- —Thermal management of junction temperatures
  - » All die subjected to uniform stress
    - V, T, ramp

# **Three-Layer Probe Isolates Challenges**

### Can optimize each piece

- -Multiple layers for high density routing
- -Compliant material to "soak up" nonplanarities
- —Robust probe points for probing Al pads





# **Existence Theorm**

- Matsushita Electric Industrial Co. Ltd has developed a 3 layer probe card
  - -Membrane-type probe points
  - -Compliant z-axis conductor
  - -Glass substrate multilayer
- Probe card components Cte-matched to Silicon
- Uses atmospheric pressure for contact force



# WLBT System

- Wafer cassette incorporating probe card
- Cassette Loader/Unloader based on auto-prober
- Standard wafer-handling equipment
- System development focuses on interface specifications







Wafer Cassette



Wafer Level Burn-in System

# **Potential WLBI**

### System market

| 8'' wafers/day           | 1996  | 1997  | 1998     | 1999        | 2000         |
|--------------------------|-------|-------|----------|-------------|--------------|
| 16M DRAM                 | 15353 | 17890 | 22696    | 15293       | 9753         |
| 64M DRAM                 | 674   | 5721  | 15825    | 44033       | 72849        |
| 256M DRAM                | 0     | 0     | 0        | 1715        | 1353         |
| 1M SRAM                  | 6279  | 10022 | 13063    | 16082       | 18400        |
| (32 bit+) µP             | 4789  | 6082  | 7173     | 7940        | 9058         |
| Candidate Product (wafer | 27096 | 39715 | 58756    | 85063       | 111414       |
| New capacity this year   |       | 12619 | 19041    | 26307       | 26351        |
| % WLBI                   | 0%    | 0%    | 0.001%   | 0.050%      | 2.000%       |
| \$450K/x10 station       | \$0   | \$0   | \$26,440 | \$1,887,478 | \$98,358,411 |



# **WLBT System Wish List**

### Probe Card

—<\$10K

—100% yield

—Quick Turn

### Cassettes

-Controlled environment

—One design fits particular wafer size (150mm, 200mm, 300mm, . . . )

# Utilize existing equipment for off-line alignment station and test electronics

-Greatly improved equipment utilization

# Quick Turn Multilayer Interconnect Using LDW



Cut Site

# **WLTB Probe Laboratory**



Mechanical Fixture



- Test Electronics
  - Up to 2000 pins
  - Total Current source up to 330A @ 8.0V

#### Mechanical Fixture

- Wafer Size Up to 8"
- Force 4 6000 lbs, 2 lb resolution
- Alignment +/-0.5 mils
- Planarization Self-Planarizing
- Chuck Vacuum chuck with active cooling

Interview of the second sec